

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/756,622
 Filing Date January 12, 2004
 Confirmation No. 1635
 Inventor J. Brett Rolfson
 Assignee Micron Technology, Inc.
 Group Art Unit 1763
 Examiner George A. Goudreau
 Attorney's Docket No. MI22-2482
 Customer No. 021567
 Title: Ion Implant Lithography Method of Processing a Semiconductor
 Substrate

RESPONSE TO DECEMBER 7, 2004 OFFICE ACTION

To: Mail Stop Amendment
 Commissioner for Patents
 P. O. Box 1450
 Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
 Wells St. John P.S.
 601 West First Avenue, Suite 1300
 Spokane, WA 99201-3828

Responsive to the Office Action dated December 7, 2004, Applicant
 amends and remarks as follows:

AMENDMENTS